

L Number	Hits	Search Text	DB	Time stamp
1	0	(Thakur.in. or Micron.as.) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near2 (precursor or reactant or gas\$4 or vapor or reagent))) and (anneal\$3 with (light or lamp))	USPAT; US-PGPUB	2003/09/25 08:58
2	0	(Thakur.in. or Micron.as.) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent))) and (anneal\$3 with (light or lamp))	USPAT; US-PGPUB	2003/09/25 09:42
3	0	(Thakur.in. or Micron.as.) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent))) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp))	USPAT; US-PGPUB	2003/09/25 08:59
4	1	(Thakur.in. or Micron.as.) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent))) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp or UV or ultraviolet or radiation or (ultra adj violet)))	USPAT; US-PGPUB	2003/09/25 09:00
5	72	(Thakur.in. or Micron.as.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp or radiation))	USPAT; US-PGPUB	2003/09/25 09:51
6	1	((Thakur.in. or Micron.as.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp or radiation))) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent)))	USPAT; US-PGPUB	2003/09/25 09:04
7	12	(Thakur.in. or Micron.as.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp or radiation))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 09:01
8	0	((Thakur.in. or Micron.as.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4)) with (light or lamp or radiation))) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent)))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 09:05
9	2	"20020119674" or "6281511"	USPAT; US-PGPUB	2003/09/25 09:23
10	362	(427/492,582,583,584).CCLS.	USPAT; US-PGPUB	2003/09/25 09:42
11	1235	(427/553,557,558,559).CCLS.	USPAT; US-PGPUB	2003/09/25 09:23
12	2190	(427/250,255.7).CCLS.	USPAT; US-PGPUB	2003/09/25 09:24
13	1519	(117/84,88,89,93,102,104,105).CCLS.	USPAT; US-PGPUB	2003/09/25 09:24
14	764	(438/680,681).CCLS.	USPAT; US-PGPUB	2003/09/25 09:24
15	520	(438/788,792).CCLS.	USPAT; US-PGPUB	2003/09/25 09:24
16	6335	((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.)	USPAT; US-PGPUB	2003/09/25 09:25
17	15	((117/84,88,89,93,102,104,105).CCLS.) and (((427/492,582,583,584).CCLS.) or ((427/553,557,558,559).CCLS.) or ((438/788,792).CCLS.))	USPAT; US-PGPUB	2003/09/25 09:31

18	38	((117/84,88,89,93,102,104,105).CCLS.) and (photoanneal\$3 or (photo adj anneal\$3) or ((anneal or bake or baked or baking or (heat adj treat\$4)) with (photo\$9 or light or lamp)))	USPAT; US-PGPUB	2003/09/25 09:36
19	60	((117/84,88,89,93,102,104,105).CCLS.) and (photoanneal\$3 or (photo adj anneal\$3) or ((anneal\$3 or RTA or bake or baked or baking or (heat adj treat\$4)) with (photo\$9 or light or lamp)))	USPAT; US-PGPUB	2003/09/25 09:36
20	60	((427/492,582,583,584).CCLS.) or ((427/553,557,558,559).CCLS.) and (ALE or ALD or (atomic adj layer adj (deposit\$3 or epitax\$8)) or (puls\$3 near4 (precursor or reactant or gas\$4 or vapor or reagent)))	USPAT; US-PGPUB	2003/09/25 09:51
21	6	((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4) with (light or lamp or ray) with (between or inbetween) with puls\$3)	USPAT; US-PGPUB	2003/09/25 09:53
22	2	((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (between or inbetween) with puls\$3 with (material or gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))	USPAT; US-PGPUB	2003/09/25 09:59
23	32	((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with puls\$3 with (material or gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))	USPAT; US-PGPUB	2003/09/25 09:56

24	29	((((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.)) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with puls\$3 with (material or gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))) not (((427/492,582,583,584).CCLS.) ((427/553,557,558,559).CCLS.) ((427/250,255.7).CCLS.) ((117/84,88,89,93,102,104,105).CCLS.) ((438/680,681).CCLS.) ((438/788,792).CCLS.)) and ((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4) with (light or lamp or ray) with (between or inbetween) with puls\$3)))	USPAT; US-PGPUB	2003/09/25 09:56
25	179	((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (between or inbetween) with puls\$3 with (material or gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))	USPAT; US-PGPUB	2003/09/25 10:32
26	86	((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (between or inbetween) with puls\$3 with (gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))	USPAT; US-PGPUB	2003/09/25 10:02
27	58	((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) same (ALE or ALD or (atomic adj layer adj (deposit\$3 or coat\$3 or epitax\$7))))	USPAT; US-PGPUB	2003/09/25 10:07
28	159	((light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (ALE or ALD or (atomic adj layer adj (deposit\$3 or coat\$3 or epitax\$7))))	USPAT; US-PGPUB	2003/09/25 10:28
29	201	((light or lamp or ray or IR or infared or infrared or UV or ultraviolet or photo\$9) with (ALE or ALD or (atomic adj layer adj (deposit\$3 or coat\$3 or epitax\$7))))	USPAT; US-PGPUB	2003/09/25 10:15
30	6	(anneal\$3 with (between or inbetween) with (puls\$3) with (precursor or gas\$4 or vapor\$4 or fluid or reactant or reagent))	USPAT; US-PGPUB	2003/09/25 10:34
31	64	(anneal\$3 with (light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared)) and (ALD or ALE or (atomic adj layer adj (deposit\$3 or epitax\$8)))	USPAT; US-PGPUB	2003/09/25 10:22
32	491	(anneal\$3 with (light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared)) and (puls\$3 near4 (material or reactant or reagent or source or precursor or gas\$4 or vapor\$4))	USPAT; US-PGPUB	2003/09/25 10:24
33	266	(anneal\$3 with (light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared)) and (puls\$3 near4 (material or reactant or reagent or precursor or gas\$4 or vapor\$4))	USPAT; US-PGPUB	2003/09/25 10:30

34	98	(anneal\$3 with (light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared)) and (puls\$3 near4 (reactant or reagent or precursor or gas\$4 or vapor\$4))	USPAT; US-PGPUB	2003/09/25 10:26
35	1193	(light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared) with (puls\$3 near4 (reactant or reagent or precursor or gas\$4 or vapor\$4))	USPAT; US-PGPUB	2003/09/25 10:27
36	37	(light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared) with (puls\$3 near4 (precursor))	USPAT; US-PGPUB	2003/09/25 10:31
37	33	((light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (ALE or ALD or (atomic adj layer adj (deposit\$3 or coat\$3 or epitax\$7))))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 10:29
38	38	((photo\$9 or light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (ALE or ALD or (atomic adj layer adj (deposit\$3 or coat\$3 or epitax\$7))))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 10:29
39	452	((anneal\$3 or bake or baked or baking or (heat\$3 adj treat\$4)) with (light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared)) and (puls\$3 near4 (material or reactant or reagent or precursor or gas\$4 or vapor\$4))	USPAT; US-PGPUB	2003/09/25 10:31
40	5	(light or photo\$9 or ray or radiation or UV or ultraviolet or infrared or infared) with (puls\$3 near4 (precursor))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 10:31
41	74	((anneal\$3 or bake or baked or baking or (heat adj treat\$4) or irradiat\$3 or radiat\$4 or expos\$4) with (light or lamp or ray or IR or infared or infrared or UV or ultraviolet) with (between or inbetween) with puls\$3 with (material or gas\$4 or reactant or purg\$3 or vapor\$3 or reagent or precursor))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 10:33
42	1	(anneal\$3 with (between or inbetween) with (puls\$3) with (precursor or gas\$4 or vapor\$4 or fluid or reactant or reagent))	EPO; JPO; DERWENT; IBM_TDB	2003/09/25 10:34